=> d his

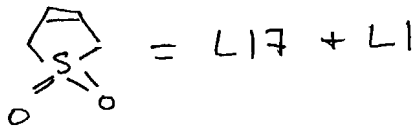
(FILE 'HOME' ENTERED AT 14:33:52 ON 25 FEB 2004)

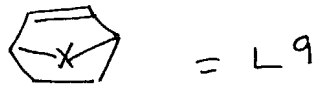
FILE 'REGISTRY' ENTERED AT 14:34:05 ON 25 FEB 2004

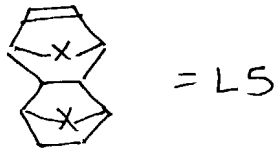
L1 31 S 77-79-2/CRN
L2 SCREEN 2067
L3 STRUCTURE UPLOADED
L4 QUE L3 AND L2
L5 0 S L4 SSS SAM
L6 SCREEN 2067
L7 STRUCTURE UPLOADED
L8 QUE L7 AND L6
L9 26 S L8 SSS SAM
L10 SCREEN 2067
L11 STRUCTURE UPLOADED
L12 QUE L11 AND L10
L13 50 S L12 SSS SAM
L14 SCREEN 2067
L15 STRUCTURE UPLOADED
L16 QUE L15 AND L14
L17 2 S L16 SSS SAM
L18 31 S L1 OR L17
L19 0 S L18 AND L9
L20 0 S L18 AND L13
L21 SCREEN 970 AND 2067
L22 STRUCTURE UPLOADED
L23 QUE L22 AND L21
L24 50 S L23
L25 50 S L23 SSS SAM
L26 0 S L18 AND L25

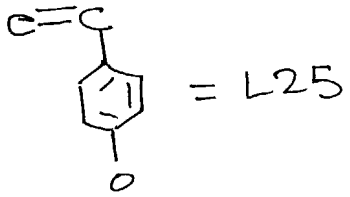
FILE 'CAPLUS, USPATFULL, HCAPLUS' ENTERED AT 14:39:29 ON 25 FEB 2004

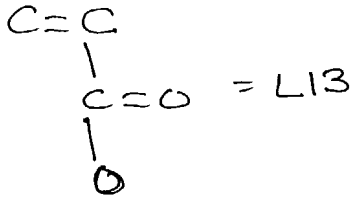
L27 0 S L26
L28 0 S L19
L29 34 S L18
L30 0 S L20
L31 1 S L29 AND (NORBORNENE)
L32 6 S L29 AND STYRENE
L33 7 S L29 AND (ACRYLATE OR METHACRYLATE)
L34 5 DUPLICATE REMOVE L33 (2 DUPLICATES REMOVED)











=> s l10 and (resist or photoresist)
L11 3 L10 AND (RESIST OR PHOTORESIST)

=> d l11 1-3 ibib hitstr

L11 ANSWER 1 OF 3 CAPLUS COPYRIGHT 2004 ACS on STN
ACCESSION NUMBER: 2003:757174 CAPLUS
DOCUMENT NUMBER: 139:267990
TITLE: Polymer having butadiene sulfone repeating unit and **resist** composition comprising the same
INVENTOR(S): Choi, Sang-Jun; Han, Woo-Sung; Woo, Sang-Gyun
PATENT ASSIGNEE(S): S. Korea
SOURCE: U.S. Pat. Appl. Publ., 9 pp.
CODEN: USXXCO
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2003180661	A1	20030925	US 2003-384727	20030311

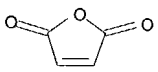
PRIORITY APPLN. INFO.: KR 2002-13265 A 20020312

4-25-03 3-11-03
not prior art.

IT **602327-84-4P 602327-85-5P 602327-86-6P**
602327-87-7P 602327-88-8P 602327-89-9P
602327-90-2P 602327-91-3P
RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(polymer having butadiene sulfone repeating unit for **resist** composition)
RN 602327-84-4 CAPLUS
CN 2,5-Furandione, polymer with 2,5-dihydrothiophene 1,1-dioxide (9CI) (CA INDEX NAME)

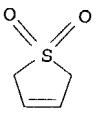
CM 1

CRN 108-31-6
CMF C4 H2 O3



CM 2

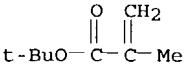
CRN 77-79-2
CMF C4 H6 O2 S



RN 602327-85-5 CAPLUS
CN 2-Propenoic acid, 2-methyl-, 1,1-dimethylethyl ester, polymer with 2,5-dihydrothiophene 1,1-dioxide and 2,5-furandione (9CI) (CA INDEX NAME)

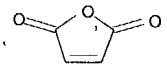
CM 1

CRN 585-07-9
CMF C8 H14 O2



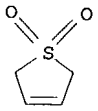
CM 2

CRN 108-31-6
CMF C4 H2 O3



CM 3

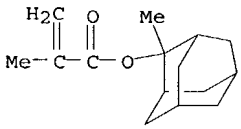
CRN 77-79-2
CMF C4 H6 O2 S



RN 602327-86-6 CAPLUS
CN 2-Propenoic acid, 2-methyl-, 2-methyltricyclo[3.3.1.13,7]dec-2-yl ester, polymer with 2,5-dihydrothiophene 1,1-dioxide and 2,5-furandione (9CI) (CA INDEX NAME)

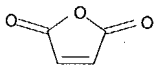
CM 1

CRN 177080-67-0
CMF C15 H22 O2



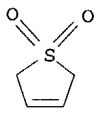
CM 2

CRN 108-31-6
CMF C4 H2 O3



CM 3

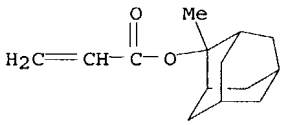
CRN 77-79-2
CMF C4 H6 O2 S



RN 602327-87-7 CAPLUS
CN 2-Propenoic acid, 2-methyltricyclo[3.3.1.13,7]dec-2-yl ester, polymer with 2,5-dihydrothiophene 1,1-dioxide and 2,5-furandione (9CI) (CA INDEX NAME)

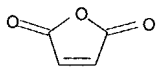
CM 1

CRN 249562-06-9
CMF C14 H20 O2



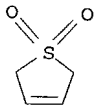
CM 2

CRN 108-31-6
CMF C4 H2 O3



CM 3

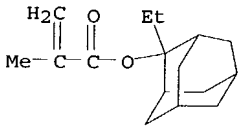
CRN 77-79-2
CMF C4 H6 O2 S



RN 602327-88-8 CAPLUS
CN 2-Propenoic acid, 2-methyl-, 2-ethyltricyclo[3.3.1.13,7]dec-2-yl ester, polymer with 2,5-dihydrothiophene 1,1-dioxide and 2,5-furandione (9CI) (CA INDEX NAME)

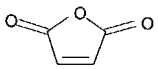
CM 1

CRN 209982-56-9
CMF C16 H24 O2



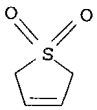
CM 2

CRN 108-31-6
CMF C4 H2 O3



CM 3

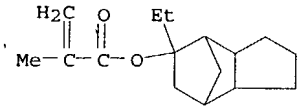
CRN 77-79-2
CMF C4 H6 O2 S



RN 602327-89-9 CAPLUS
CN 2-Propenoic acid, 2-methyl-, 5-ethyloctahydro-4,7-methano-1H-inden-5-yl ester, polymer with 2,5-dihydrothiophene 1,1-dioxide and 2,5-furandione (9CI) (CA INDEX NAME)

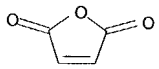
CM 1

CRN 348089-09-8
CMF C16 H24 O2



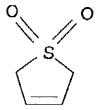
CM 2

CRN 108-31-6
CMF C4 H2 O3



CM 3

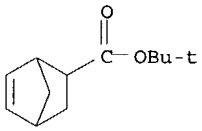
CRN 77-79-2
CMF C4 H6 O2 S



RN 602327-90-2 CAPLUS
CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 1,1-dimethylethyl ester, polymer with 2,5-dihydrothiophene 1,1-dioxide and 2,5-furandione (9CI) (CA INDEX NAME)

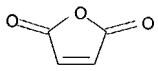
CM 1

CRN 154970-45-3
CMF C12 H18 O2



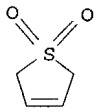
CM 2

CRN 108-31-6
CMF C4 H2 O3



CM 3

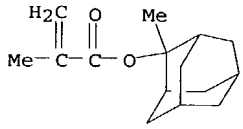
CRN 77-79-2
CMF C4 H6 O2 S



RN 602327-91-3 CAPLUS
CN 2-Propenoic acid, 2-methyl-, 2-methyltricyclo[3.3.1.13,7]dec-2-yl ester, polymer with bicyclo[2.2.1]hept-2-ene, 2,5-dihydrothiophene 1,1-dioxide and 2,5-furandione (9CI) (CA INDEX NAME)

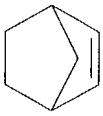
CM 1

CRN 177080-67-0
CMF C15 H22 O2



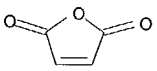
CM 2

CRN 498-66-8
CMF C7 H10



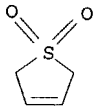
CM 3

CRN 108-31-6
CMF C4 H2 O3



CM 4

CRN 77-79-2
CMF C4 H6 O2 S



L11 ANSWER 2 OF 3 CAPLUS COPYRIGHT 2004 ACS on STN
ACCESSION NUMBER: 2003:77399 CAPLUS
DOCUMENT NUMBER: 138:145060
TITLE: **Photoresist** monomers, polymers thereof and **photoresist** compositions containing the same
INVENTOR(S): Lee, Geun Su; Jung, Jae Chang; Shin, Ki Soo
PATENT ASSIGNEE(S): S. Korea
SOURCE: U.S. Pat. Appl. Publ., 15 pp.
CODEN: USXXCO
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

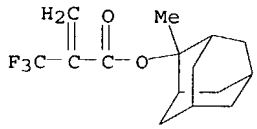
present

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2003022100	A1	20030130	US 2002-54532	20020122

PRIORITY APPLN. INFO.: KR 2001-38118 A 20010629
IT **492468-79-8P 492468-80-1P 492468-81-2P**
492468-82-3P 492468-83-4DP, 4-Acetoxy styrene-butadiene sulfone copolymer, hydrolyzed and react with ethylvinylether
RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(**photoresist** monomers and polymers for **photoresist** compns.)
RN 492468-79-8 CAPLUS
CN 2-Propenoic acid, 2-(trifluoromethyl)-, 2-methyltricyclo[3.3.1.13,7]dec-2-yl ester, polymer with bicyclo[2.2.1]hept-2-ene and 2,5-dihydrothiophene 1,1-dioxide (9CI) (CA INDEX NAME)

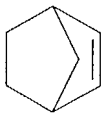
CM 1

CRN 188739-86-8
CMF C15 H19 F3 O2



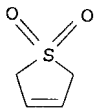
CM 2

CRN 498-66-8
CMF C7 H10



CM 3

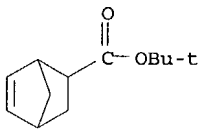
CRN 77-79-2
CMF C4 H6 O2 S



RN 492468-80-1 CAPLUS
CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 1,1-dimethylethyl ester, polymer with 2,5-dihydrothiophene 1,1-dioxide and 2,2,2-trifluoro-1-(trifluoromethyl)ethyl 2-(trifluoromethyl)-2-propenoate (9CI) (CA INDEX NAME)

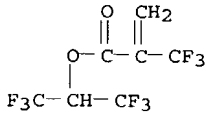
CM 1

CRN 154970-45-3
CMF C12 H18 O2



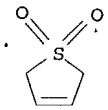
CM 2

CRN 91520-41-1
CMF C7 H3 F9 O2



CM 3

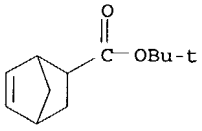
CRN 77-79-2
CMF C4 H6 O2 S



RN 492468-81-2 CAPLUS
CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 1,1-dimethylethyl ester, polymer with 2,5-dihydrothiophene 1,1-dioxide and 2,2,2-trifluoro-1-(trifluoromethyl)ethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

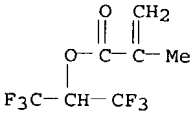
CM 1

CRN 154970-45-3
CMF C12 H18 O2



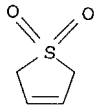
CM 2

CRN 3063-94-3
CMF C7 H6 F6 O2



CM 3

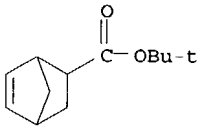
CRN 77-79-2
CMF C4 H6 O2 S



RN 492468-82-3 CAPLUS
CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 1,1-dimethylethyl ester, polymer with 2,5-dihydrothiophene 1,1-dioxide, 1-methyl-1H-pyrrole-2,5-dione and 2,2,2-trifluoro-1-(trifluoromethyl)ethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

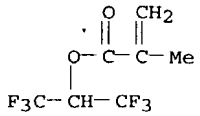
CM 1

CRN 154970-45-3
CMF C12 H18 O2



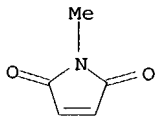
CM 2

CRN 3063-94-3
CMF C7 H6 F6 O2



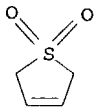
CM 3

CRN 930-88-1
CMF C5 H5 N O2



CM 4

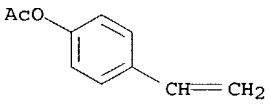
CRN 77-79-2
CMF C4 H6 O2 S



RN 492468-83-4 CAPLUS
CN Phenol, 4-ethenyl-, acetate, polymer with 2,5-dihydrothiophene 1,1-dioxide (9CI) (CA INDEX NAME)

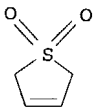
CM 1

CRN 2628-16-2
CMF C10 H10 O2



CM 2

CRN 77-79-2
CMF C4 H6 O2 S



L11 ANSWER 3 OF 3 CAPLUS COPYRIGHT 2004 ACS on STN
ACCESSION NUMBER: 2002:767931 CAPLUS
DOCUMENT NUMBER: 137:302211
TITLE: Ring-containing monomers, polymers for **resists**, photopolymer compositions, and their use in pattern formation and electronic part manufacture
INVENTOR(S): Shinoda, Naomi; Gokochi, Toru
PATENT ASSIGNEE(S): Toshiba Corp., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 27 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE

JP 2002293829 A2 20021009 JP 2001-98186 20010330
PRIORITY APPLN. INFO.: JP 2001-98186 20010330

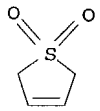
10-9-02

IT **26745-92-6P 467418-78-6P**, Acrylonitrile-2,5-dihydrothiophene 1,1-dioxide copolymer
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(ring-containing monomers, polymers for **resists**, photopolymer compns., and their use in pattern formation and electronic part manufacture)

RN 26745-92-6 CAPLUS
CN Thiophene, 2,5-dihydro-, 1,1-dioxide, homopolymer (9CI) (CA INDEX NAME)

CM 1

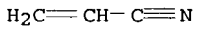
CRN 77-79-2 ✓
CMF C4 H6 O2 S



RN 467418-78-6 CAPLUS
CN 2-Propenenitrile, polymer with 2,5-dihydrothiophene 1,1-dioxide (9CI) (CA INDEX NAME)

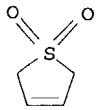
CM 1

CRN 107-13-1
CMF C3 H3 N



CM 2

CRN 77-79-2 ✓
CMF C4 H6 O2 S



L32 ANSWER 1 OF 6 CAPLUS COPYRIGHT 2004 ACS on STN
ACCESSION NUMBER: 2003:77399 CAPLUS
DOCUMENT NUMBER: 138:145060
TITLE: Photoresist monomers, polymers thereof and photoresist compositions containing the same
INVENTOR(S): Lee, Geun Su; Jung, Jae Chang; Shin, Ki Soo
PATENT ASSIGNEE(S): S. Korea
SOURCE: U.S. Pat. Appl. Publ., 15 pp.
CODEN: USXXCO
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2003022100	A1	20030130	US 2002-54532	20020122

PRIORITY APPLN. INFO.: KR 2001-38118 A 20010629

present

L32 ANSWER 2 OF 6 CAPLUS COPYRIGHT 2004 ACS on STN
ACCESSION NUMBER: 1987:85678 CAPLUS
DOCUMENT NUMBER: 106:85678
TITLE: Preparation of connected block branched polypropylene glycols for urethane foam manufacture.
INVENTOR(S): Taylor, Glenn Alfred; Hoy, Kenneth Look
PATENT ASSIGNEE(S): Union Carbide Corp., USA
SOURCE: Eur. Pat. Appl., 80 pp.
CODEN: EPXXDW
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 131209	A2	19850116	EP 1984-107465	19840628
EP 131209	A3	19860430		
R: AT, BE, CH, DE, FR, GB, IT, LI, LU, NL, SE				
CA 1225093	A1	19870804	CA 1984-455585	19840531
AU 8429941	A1	19850103	AU 1984-29941	19840627
AU 576768	B2	19880908		
JP 60020915	A2	19850202	JP 1984-132153	19840628
BR 8403188	A	19850611	BR 1984-3188	19840628
US 4594366	A	19860610	US 1984-679611	19841207

PRIORITY APPLN. INFO.: US 1983-509089 19830629
US 1983-562453 19831220

L32 ANSWER 3 OF 6 USPATFULL on STN
ACCESSION NUMBER: 2003:30154 USPATFULL
TITLE: Photoresist monomers, polymers thereof and photoresist compositions containing the same
INVENTOR(S): Lee, Geun Su, Kyoungki-do, KOREA, REPUBLIC OF
Jung, Jae Chang, Kyoungki-do, KOREA, REPUBLIC OF
Shin, Ki Soo, Kyoungki-do, KOREA, REPUBLIC OF

present

	NUMBER	KIND	DATE	
PATENT INFORMATION:	US 2003022100	A1	20030130	
APPLICATION INFO.:	US 2002-54532	A1	20020122	(10)

	NUMBER	DATE
PRIORITY INFORMATION:	KR 2001-38118	20010629

DOCUMENT TYPE: Utility
FILE SEGMENT: APPLICATION
LEGAL REPRESENTATIVE: MARSHALL, GERSTEIN & BORUN, 6300 SEARS TOWER, 233 SOUTH WACKER, CHICAGO, IL, 60606-6357
NUMBER OF CLAIMS: 28
EXEMPLARY CLAIM: 1
NUMBER OF DRAWINGS: 4 Drawing Page(s)
LINE COUNT: 659
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L32 ANSWER 4 OF 6 USPATFULL on STN
ACCESSION NUMBER: 86:34258 USPATFULL
TITLE: Connected branched polyols and polyurethanes based thereon
INVENTOR(S): Taylor, Glenn A., South Charleston, WV, United States
Hoy, Kenneth L., Saint Albans, WV, United States
PATENT ASSIGNEE(S): Union Carbide Corporation, Danbury, CT, United States (U.S. corporation)

	NUMBER	KIND	DATE

PATENT INFORMATION:	US 4594366		19860610
APPLICATION INFO.:	US 1984-679611		19841207 (6)
RELATED APPLN. INFO.:	Continuation-in-part of Ser. No. US 1983-562453, filed on 20 Dec 1983, now abandoned which is a continuation of Ser. No. US 1983-509089, filed on 29 Jun 1983, now abandoned		
DOCUMENT TYPE:	Utility		
FILE SEGMENT:	Granted		
PRIMARY EXAMINER:	Cockeram, Herbert S.		
LEGAL REPRESENTATIVE:	Leuzzi, P. W.		
NUMBER OF CLAIMS:	52		
EXEMPLARY CLAIM:	1,18		
LINE COUNT:	2396		

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L32 ANSWER 5 OF 6 HCAPLUS COPYRIGHT 2004 ACS on STN

ACCESSION NUMBER:	2003:77399 HCAPLUS
DOCUMENT NUMBER:	138:145060
TITLE:	Photoresist monomers, polymers thereof and photoresist compositions containing the same
INVENTOR(S):	Lee, Geun Su; Jung, Jae Chang; Shin, Ki Soo
PATENT ASSIGNEE(S):	S. Korea
SOURCE:	U.S. Pat. Appl. Publ., 15 pp. CODEN: USXXCO
DOCUMENT TYPE:	Patent
LANGUAGE:	English
FAMILY ACC. NUM. COUNT:	1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2003022100	A1	20030130	US 2002-54532	20020122
PRIORITY APPLN. INFO.:			KR 2001-38118 A	20010629

present

L32 ANSWER 6 OF 6 HCAPLUS COPYRIGHT 2004 ACS on STN

ACCESSION NUMBER:	1987:85678 HCAPLUS
DOCUMENT NUMBER:	106:85678
TITLE:	Preparation of connected block branched polypropylene glycols for urethane foam manufacture.
INVENTOR(S):	Taylor, Glenn Alfred; Hoy, Kenneth Look
PATENT ASSIGNEE(S):	Union Carbide Corp., USA
SOURCE:	Eur. Pat. Appl., 80 pp. CODEN: EPXXDW
DOCUMENT TYPE:	Patent
LANGUAGE:	English
FAMILY ACC. NUM. COUNT:	1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 131209	A2	19850116	EP 1984-107465	19840628
EP 131209	A3	19860430		
R: AT, BE, CH, DE, FR, GB, IT, LI, LU, NL, SE				
CA 1225093	A1	19870804	CA 1984-455585	19840531
AU 8429941	A1	19850103	AU 1984-29941	19840627
AU 576768	B2	19880908		
JP 60020915	A2	19850202	JP 1984-132153	19840628
BR 8403188	A	19850611	BR 1984-3188	19840628
US 4594366	A	19860610	US 1984-679611	19841207
PRIORITY APPLN. INFO.:			US 1983-509089	19830629
			US 1983-562453	19831220

L34 ANSWER 1 OF 5 USPATFULL on STN
ACCESSION NUMBER: 2003:257610 USPATFULL
TITLE: Polymer having butadiene sulfone repeating unit and resist composition comprising the same
INVENTOR(S): Choi, Sang-jun, Seoul, KOREA, REPUBLIC OF
Han, Woo-sung, Seoul, KOREA, REPUBLIC OF
Woo, Sang-gyun, Yongin-city, KOREA, REPUBLIC OF

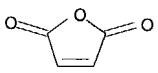
	NUMBER	KIND	DATE
PATENT INFORMATION:	US 2003180661	A1	20030925
APPLICATION INFO.:	US 2003-384727	A1	20030311 (10)

	NUMBER	DATE
PRIORITY INFORMATION:	KR 2002-13265	20020312

DOCUMENT TYPE: Utility
FILE SEGMENT: APPLICATION
LEGAL REPRESENTATIVE: LEE & STERBA, PC, Suite 2000, 1101 Wilson Boulevard, Arlington, VA, 22209
NUMBER OF CLAIMS: 54
EXEMPLARY CLAIM: 1
LINE COUNT: 551
CAS INDEXING IS AVAILABLE FOR THIS PATENT.
IT **602327-84-4P 602327-85-5P 602327-86-6P**
602327-87-7P 602327-88-8P 602327-89-9P
602327-90-2P 602327-91-3P
(polymer having butadiene sulfone repeating unit for resist composition)
RN 602327-84-4 USPATFULL
CN 2,5-Furandione, polymer with 2,5-dihydrothiophene 1,1-dioxide (9CI) (CA INDEX NAME)

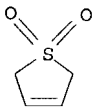
CM 1

CRN 108-31-6
CMF C4 H2 O3



CM 2

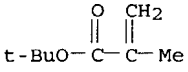
CRN 77-79-2
CMF C4 H6 O2 S



RN 602327-85-5 USPATFULL
CN 2-Propenoic acid, 2-methyl-, 1,1-dimethylethyl ester, polymer with 2,5-dihydrothiophene 1,1-dioxide and 2,5-furandione (9CI) (CA INDEX NAME)

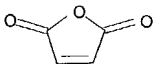
CM 1

CRN 585-07-9
CMF C8 H14 O2



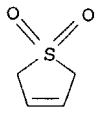
CM 2

CRN 108-31-6
CMF C4 H2 O3



CM 3

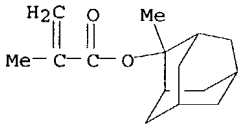
CRN 77-79-2
CMF C4 H6 O2 S



RN 602327-86-6 USPATFULL
CN 2-Propenoic acid, 2-methyl-, 2-methyltricyclo[3.3.1.13,7]dec-2-yl ester, polymer with 2,5-dihydrothiophene 1,1-dioxide and 2,5-furandione (9CI) (CA INDEX NAME)

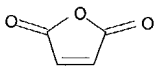
CM 1

CRN 177080-67-0
CMF C15 H22 O2



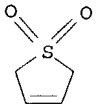
CM 2

CRN 108-31-6
CMF C4 H2 O3



CM 3

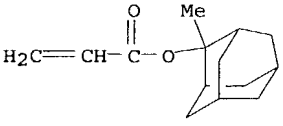
CRN 77-79-2
CMF C4 H6 O2 S



RN 602327-87-7 USPATFULL
CN 2-Propenoic acid, 2-methyltricyclo[3.3.1.13,7]dec-2-yl ester, polymer with 2,5-dihydrothiophene 1,1-dioxide and 2,5-furandione (9CI) (CA INDEX NAME)

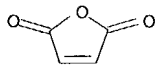
CM 1

CRN 249562-06-9
CMF C14 H20 O2



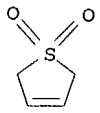
CM 2

CRN 108-31-6
CMF C4 H2 O3



CM 3

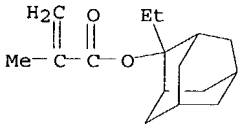
CRN 77-79-2
CMF C4 H6 O2 S



RN 602327-88-8 USPATFULL
CN 2-Propenoic acid, 2-methyl-, 2-ethyltricyclo[3.3.1.13,7]dec-2-yl ester, polymer with 2,5-dihydrothiophene 1,1-dioxide and 2,5-furandione (9CI) (CA INDEX NAME)

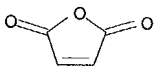
CM 1

CRN 209982-56-9
CMF C16 H24 O2



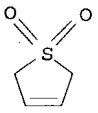
CM 2

CRN 108-31-6
CMF C4 H2 O3



CM 3

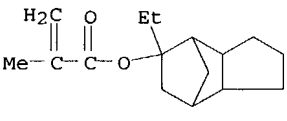
CRN 77-79-2
CMF C4 H6 O2 S



RN 602327-89-9 USPATFULL
CN 2-Propenoic acid, 2-methyl-, 5-ethyloctahydro-4,7-methano-1H-inden-5-yl ester, polymer with 2,5-dihydrothiophene 1,1-dioxide and 2,5-furandione (9CI) (CA INDEX NAME)

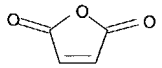
CM 1

CRN 348089-09-8
CMF C16 H24 O2



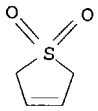
CM 2

CRN 108-31-6
CMF C4 H2 O3



CM 3

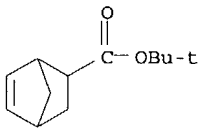
CRN 77-79-2
CMF C4 H6 O2 S



RN 602327-90-2 USPATFULL
CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 1,1-dimethylethyl ester, polymer with 2,5-dihydrothiophene 1,1-dioxide and 2,5-furandione (9CI) (CA INDEX NAME)

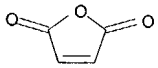
CM 1

CRN 154970-45-3
CMF C12 H18 O2



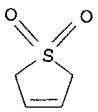
CM 2

CRN 108-31-6
CMF C4 H2 O3



CM 3

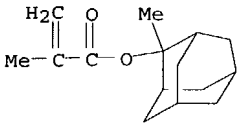
CRN 77-79-2
CMF C4 H6 O2 S



RN 602327-91-3 USPATFULL
CN 2-Propenoic acid, 2-methyl-, 2-methyltricyclo[3.3.1.13,7]dec-2-yl ester, polymer with bicyclo[2.2.1]hept-2-ene, 2,5-dihydrothiophene 1,1-dioxide and 2,5-furandione (9CI) (CA INDEX NAME)

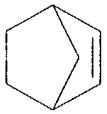
CM 1

CRN 177080-67-0
CMF C15 H22 O2



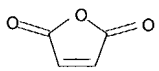
CM 2

CRN 498-66-8
CMF C7 H10



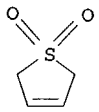
CM 3

CRN 108-31-6
CMF C4 H2 O3



CM 4

CRN 77-79-2
CMF C4 H6 O2 S



L34 ANSWER 2 OF 5 USPATFULL on STN
ACCESSION NUMBER: 2003:30154 USPATFULL
TITLE: Photoresist monomers, polymers thereof and photoresist compositions containing the same
INVENTOR(S): Lee, Geun Su, Kyoungki-do, KOREA, REPUBLIC OF
Jung, Jae Chang, Kyoungki-do, KOREA, REPUBLIC OF
Shin, Ki Soo, Kyoungki-do, KOREA, REPUBLIC OF

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 2003022100	A1	20030130
APPLICATION INFO.:	US 2002-54532	A1	20020122 (10)

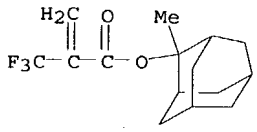
	NUMBER	DATE
PRIORITY INFORMATION:	KR 2001-38118	20010629

present

DOCUMENT TYPE: Utility
FILE SEGMENT: APPLICATION
LEGAL REPRESENTATIVE: MARSHALL, GERSTEIN & BORUN, 6300 SEARS TOWER, 233 SOUTH WACKER, CHICAGO, IL, 60606-6357
NUMBER OF CLAIMS: 28
EXEMPLARY CLAIM: 1
NUMBER OF DRAWINGS: 4 Drawing Page(s)
LINE COUNT: 659
CAS INDEXING IS AVAILABLE FOR THIS PATENT.
IT **492468-79-8P 492468-80-1P 492468-81-2P 492468-82-3P 492468-83-4DP**, 4-Acetoxy styrene-butadiene sulfone copolymer, hydrolyzed and react with ethylvinylether (photoresist monomers and polymers for photoresist compns.)
RN 492468-79-8 USPATFULL
CN 2-Propenoic acid, 2-(trifluoromethyl)-, 2-methyltricyclo[3.3.1.13,7]dec-2-yl ester, polymer with bicyclo[2.2.1]hept-2-ene and 2,5-dihydrothiophene 1,1-dioxide (9CI) (CA INDEX NAME)

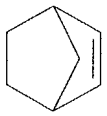
CM 1

CRN 188739-86-8
CMF C15 H19 F3 O2



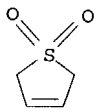
CM 2

CRN 498-66-8
CMF C7 H10



CM 3

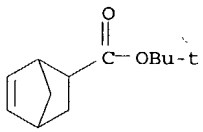
CRN 77-79-2
CMF C4 H6 O2 S



RN 492468-80-1 USPATFULL
CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 1,1-dimethylethyl ester, polymer with 2,5-dihydrothiophene 1,1-dioxide and 2,2,2-trifluoro-1-(trifluoromethyl)ethyl 2-(trifluoromethyl)-2-propenoate (9CI) (CA INDEX NAME)

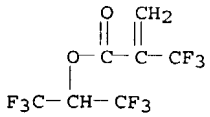
CM 1

CRN 154970-45-3
CMF C12 H18 O2



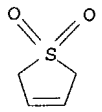
CM 2

CRN 91520-41-1
CMF C7 H3 F9 O2



CM 3

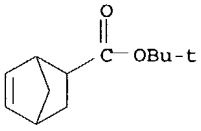
CRN 77-79-2
CMF C4 H6 O2 S



RN 492468-81-2 USPATFULL
CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 1,1-dimethylethyl ester, polymer with 2,5-dihydrothiophene 1,1-dioxide and 2,2,2-trifluoro-1-(trifluoromethyl)ethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

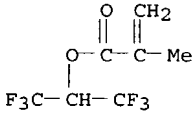
CM 1

CRN 154970-45-3
CMF C12 H18 O2



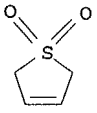
CM 2

CRN 3063-94-3
CMF C7 H6 F6 O2



CM 3

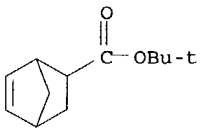
CRN 77-79-2
CMF C4 H6 O2 S



RN 492468-82-3 USPATFULL
CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 1,1-dimethylethyl ester, polymer with 2,5-dihydrothiophene 1,1-dioxide, 1-methyl-1H-pyrrole-2,5-dione and 2,2,2-trifluoro-1-(trifluoromethyl)ethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

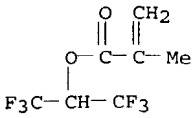
CM 1

CRN 154970-45-3
CMF C12 H18 O2



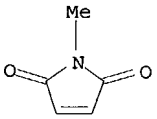
CM 2

CRN 3063-94-3
CMF C7 H6 F6 O2



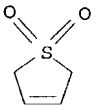
CM 3

CRN 930-88-1
CMF C5 H5 N O2



CM 4

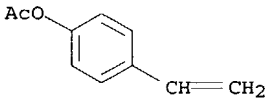
CRN 77-79-2
CMF C4 H6 O2 S



RN 492468-83-4 USPATFULL
CN Phenol, 4-ethenyl-, acetate, polymer with 2,5-dihydrothiophene 1,1-dioxide (9CI) (CA INDEX NAME)

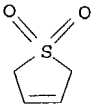
CM 1

CRN 2628-16-2
CMF C10 H10 O2



CM 2

CRN 77-79-2
CMF C4 H6 O2 S



L34 ANSWER 3 OF 5 USPATFULL on STN

ACCESSION NUMBER:	86:34258 USPATFULL
TITLE:	Connected branched polyols and polyurethanes based thereon
INVENTOR(S):	Taylor, Glenn A., South Charleston, WV, United States Hoy, Kenneth L., Saint Albans, WV, United States
PATENT ASSIGNEE(S):	Union Carbide Corporation, Danbury, CT, United States (U.S. corporation)

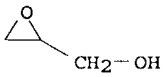
	NUMBER	KIND	DATE
PATENT INFORMATION:	US 4594366		19860610
APPLICATION INFO.:	US 1984-679611		19841207 (6)
RELATED APPLN. INFO.:	Continuation-in-part of Ser. No. US 1983-562453, filed on 20 Dec 1983, now abandoned which is a continuation of Ser. No. US 1983-509089, filed on 29 Jun 1983, now abandoned		

DOCUMENT TYPE: Utility
FILE SEGMENT: Granted
PRIMARY EXAMINER: Cockeram, Herbert S.
LEGAL REPRESENTATIVE: Leuzzi, P. W.
NUMBER OF CLAIMS: 52
EXEMPLARY CLAIM: 1,18
LINE COUNT: 2396
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

IT **106869-95-8**
(branched, for dispersion of thermoplastics in polyurethane manufacture)
RN 106869-95-8 USPATFULL
CN Thiophene, 2,5-dihydro-, 1,1-dioxide, polymer with ethenylbenzene, methyloxirane and oxiranemethanol, block, graft (9CI) (CA INDEX NAME)

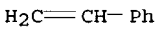
CM 1

CRN 556-52-5
CMF C3 H6 O2



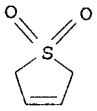
CM 2

CRN 100-42-5
CMF C8 H8



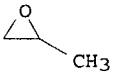
CM 3

CRN 77-79-2
CMF C4 H6 O2 S



CM 4

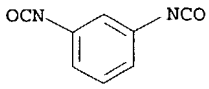
CRN 75-56-9
CMF C3 H6 O



IT **106880-20-0**
(cellular, thermoplastic additive-containing, fire-resistant, with high load-bearing capacity)
RN 106880-20-0 USPATFULL
CN 1,2,3-Propanetriol, polymer with 2,5-dihydrothiophene 1,1-dioxide, 1,3-diisocyanatomethylbenzene, ethenylbenzene, methyloxirane and oxiranemethanol, block, graft (9CI) (CA INDEX NAME)

CM 1

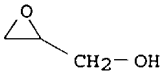
CRN 26471-62-5
CMF C9 H6 N2 O2
CCI IDS
CDES 8:ID



D1— Me

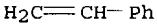
CM 2

CRN 556-52-5
CMF C3 H6 O2



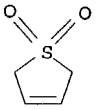
CM 3

CRN 100-42-5
CMF C8 H8



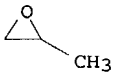
CM 4

CRN 77-79-2
CMF C4 H6 O2 S



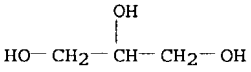
CM 5

CRN 75-56-9
CMF C3 H6 O



CM 6

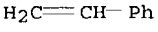
CRN 56-81-5
CMF C3 H8 O3



IT **106870-03-5**
(polyol dispersions containing thermoplastics and, for polyurethane manufacture)
RN 106870-03-5 USPATFULL
CN 1,2,3-Propanetriol, polymer with 2,5-dihydrothiophene 1,1-dioxide, ethenylbenzene, methyloxirane and oxirane, block, graft (9CI) (CA INDEX NAME)

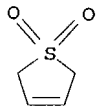
CM 1

CRN 100-42-5
CMF C8 H8



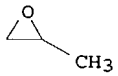
CM 2

CRN 77-79-2
CMF C4 H6 O2 S



CM 3

CRN 75-56-9
CMF C3 H6 O

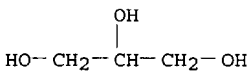


CM 4

CRN 75-21-8
CMF C2 H4 O

CM 5

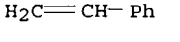
CRN 56-81-5
CMF C3 H8 O3



IT **106870-07-9**
(polyol dispersions containing, stable, for polyurethane manufacture)
RN 106870-07-9 USPATFULL
CN Thiophene, 2,5-dihydro-, 1,1-dioxide, polymer with ethenylbenzene (9CI)
(CA INDEX NAME)

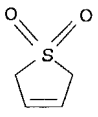
CM 1

CRN 100-42-5
CMF C8 H8



CM 2

CRN 77-79-2
CMF C4 H6 O2 S



L34 ANSWER 4 OF 5 CAPLUS COPYRIGHT 2004 ACS on STN DUPLICATE 1
ACCESSION NUMBER: 1987:85678 CAPLUS
DOCUMENT NUMBER: 106:85678
TITLE: Preparation of connected block branched polypropylene glycols for urethane foam manufacture.

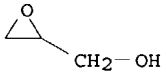
INVENTOR(S): Taylor, Glenn Alfred; Hoy, Kenneth Look
PATENT ASSIGNEE(S): Union Carbide Corp., USA
SOURCE: Eur. Pat. Appl., 80 pp.
CODEN: EPXXDW
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 131209	A2	19850116	EP 1984-107465	19840628
EP 131209	A3	19860430		
R: AT, BE, CH, DE, FR, GB, IT, LI, LU, NL, SE				
CA 1225093	A1	19870804	CA 1984-455585	19840531
AU 8429941	A1	19850103	AU 1984-29941	19840627
AU 576768	B2	19880908		
JP 60020915	A2	19850202	JP 1984-132153	19840628
BR 8403188	A	19850611	BR 1984-3188	19840628
US 4594366	A	19860610	US 1984-679611	19841207
PRIORITY APPLN. INFO.:			US 1983-509089	19830629
			US 1983-562453	19831220

IT **106869-95-8**
RL: USES (Uses)
(branched, for dispersion of thermoplastics in polyurethane manufacture)
RN 106869-95-8 CAPLUS
CN Thiophene, 2,5-dihydro-, 1,1-dioxide, polymer with ethenylbenzene, methyloxirane and oxiranemethanol, block, graft (9CI) (CA INDEX NAME)

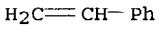
CM 1

CRN 556-52-5
CMF C3 H6 O2



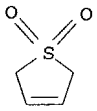
CM 2

CRN 100-42-5
CMF C8 H8



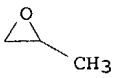
CM 3

CRN 77-79-2
CMF C4 H6 O2 S



CM 4

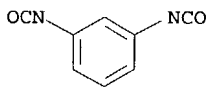
CRN 75-56-9
CMF C3 H6 O



IT **106880-20-0**
RL: USES (Uses)
(cellular, thermoplastic additive-containing, fire-resistant, with high load-bearing capacity)
RN 106880-20-0 CAPLUS
CN 1,2,3-Propanetriol, polymer with 2,5-dihydrothiophene 1,1-dioxide, 1,3-diisocyanatomethylbenzene, ethenylbenzene, methyloxirane and oxiranemethanol, block, graft (9CI) (CA INDEX NAME)

CM 1

CRN 26471-62-5
CMF C9 H6 N2 O2
CCI IDS



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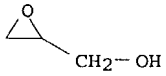
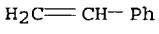
CM 2

CRN 556-52-5
CMF C3 H6 O2



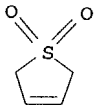
CM 3

CRN 100-42-5
CMF C8 H8



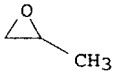
CM 4

CRN 77-79-2
CMF C4 H6 O2 S



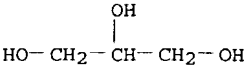
CM 5

CRN 75-56-9
CMF C3 H6 O



CM 6

CRN 56-81-5
CMF C3 H8 O3

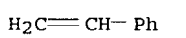


IT **106870-03-5**
RL: USES (Uses)
(polyol dispersions containing thermoplastics and, for polyurethane manufacture)
RN 106870-03-5 CAPLUS
CN 1,2,3-Propanetriol, polymer with 2,5-dihydrothiophene 1,1-dioxide, ethenylbenzene, methyloxirane and oxirane, block, graft (9CI) (CA INDEX

NAME)

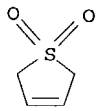
CM 1

CRN 100-42-5
CMF C8 H8



CM 2

CRN 77-79-2
CMF C4 H6 O2 S



CM 3

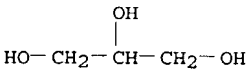
CRN 75-56-9
CMF C3 H6 O

CM 4

CRN 75-21-8
CMF C2 H4 O

CM 5

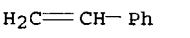
CRN 56-81-5
CMF C3 H8 O3



IT **106870-07-9**
RL: USES (Uses)
(polyol dispersions containing, stable, for polyurethane manufacture)
RN 106870-07-9 CAPLUS
CN Thiophene, 2,5-dihydro-, 1,1-dioxide, polymer with ethenylbenzene (9CI)
(CA INDEX NAME)

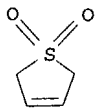
CM 1

CRN 100-42-5
CMF C8 H8



CM 2

CRN 77-79-2
CMF C4 H6 O2 S



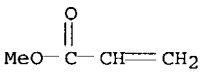
L34 ANSWER 5 OF 5 CAPLUS COPYRIGHT 2004 ACS on STN DUPLICATE 2
ACCESSION NUMBER: 1967:86765 CAPLUS
DOCUMENT NUMBER: 66:86765
TITLE: Vinylidene chloride copolymers for use as coatings
PATENT ASSIGNEE(S): CIBA Ltd.
SOURCE: Neth. Appl., 14 pp.
CODEN: NAXXAN
DOCUMENT TYPE: Patent
LANGUAGE: Dutch
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
NL 6606757		19661121		
CH 449264			CH	
DE 1595413			DE	
FR 1478817			FR	
GB 1082037			GB	
US 3449302		19690000	US	

PRIORITY APPLN. INFO.: CH 19650518
IT **31853-27-7 31853-28-8**, uses and miscellaneous
31853-29-9, uses and miscellaneous **31853-30-2**, uses and miscellaneous **31853-31-3**, uses and miscellaneous
31853-36-8 31853-37-9
RL: USES (Uses)
(coatings of)
RN 31853-27-7 CAPLUS
CN Acrylic acid, polymer with 1,1-dichloroethylene, 2,5-dihydrothiophene 1,1-dioxide and methyl acrylate (8CI) (CA INDEX NAME)

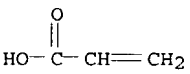
CM 1

CRN 96-33-3
CMF C4 H6 O2



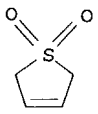
CM 2

CRN 79-10-7
CMF C3 H4 O2



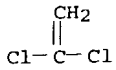
CM 3

CRN 77-79-2
CMF C4 H6 O2 S



CM 4

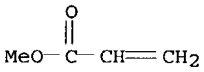
CRN 75-35-4
CMF C2 H2 Cl2



RN 31853-28-8 CAPLUS
CN Methacrylic acid, polymer with 1,1-dichloroethylene, 2,5-dihydrothiophene 1,1-dioxide and methyl acrylate (8CI) (CA INDEX NAME)

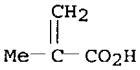
CM 1

CRN 96-33-3
CMF C4 H6 O2



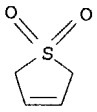
CM 2

CRN 79-41-4
CMF C4 H6 O2



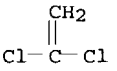
CM 3

CRN 77-79-2
CMF C4 H6 O2 S



CM 4

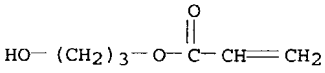
CRN 75-35-4
CMF C2 H2 Cl2



RN 31853-29-9 CAPLUS
CN Acrylic acid, 3-hydroxypropyl ester, polymer with 1,1-dichloroethylene, 2,5-dihydrothiophene 1,1-dioxide and methyl acrylate (8CI) (CA INDEX NAME)

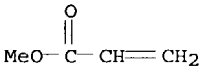
CM 1

CRN 2761-08-2
CMF C6 H10 O3



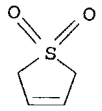
CM 2

CRN 96-33-3
CMF C4 H6 O2



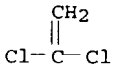
CM 3

CRN 77-79-2
CMF C4 H6 O2 S



CM 4

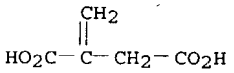
CRN 75-35-4
CMF C2 H2 Cl2



RN 31853-30-2 CAPLUS
CN Succinic acid, methylene-, polymer with 1,1-dichloroethylene, 2,5-dihydrothiophene 1,1-dioxide and methyl acrylate (8CI) (CA INDEX NAME)

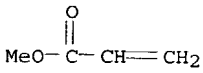
CM 1

CRN 97-65-4
CMF C5 H6 O4



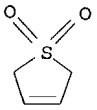
CM 2

CRN 96-33-3
CMF C4 H6 O2



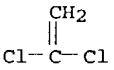
CM 3

CRN 77-79-2
CMF C4 H6 O2 S



CM 4

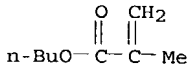
CRN 75-35-4
CMF C2 H2 Cl2



RN 31853-31-3 CAPLUS
CN Methacrylic acid, polymer with butyl methacrylate, 1,1-dichloroethylene and 2,5-dihydrothiophene 1,1-dioxide (8CI) (CA INDEX NAME)

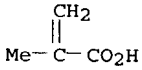
CM 1

CRN 97-88-1
CMF C8 H14 O2



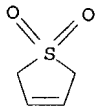
CM 2

CRN 79-41-4
CMF C4 H6 O2



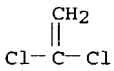
CM 3

CRN 77-79-2
CMF C4 H6 O2 S



CM 4

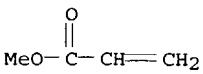
CRN 75-35-4
CMF C2 H2 Cl2



RN 31853-36-8 CAPLUS
CN Acrylic acid methyl ester, polymer with 1,1-dichloroethylene, 2,5-dihydrothiophene 1,1-dioxide and 1-vinyl-2-pyrrolidinone (8CI) (CA INDEX NAME)

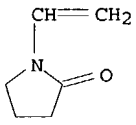
CM 1

CRN 96-33-3
CMF C4 H6 O2



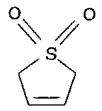
CM 2

CRN 88-12-0
CMF C6 H9 N O



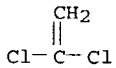
CM 3

CRN 77-79-2
CMF C4 H6 O2 S



CM 4

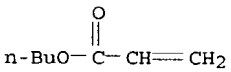
CRN 75-35-4
CMF C2 H2 Cl2



RN 31853-37-9 CAPLUS
CN Acrylic acid butyl ester, polymer with 1,1-dichloroethylene, 2,5-dihydrothiophene 1,1-dioxide and 1-vinyl-2-pyrrolidinone (8CI) (CA INDEX NAME)

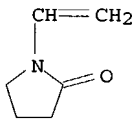
CM 1

CRN 141-32-2
CMF C7 H12 O2



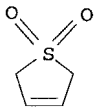
CM 2

CRN 88-12-0
CMF C6 H9 N O



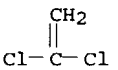
CM 3

CRN 77-79-2
CMF C4 H6 O2 S



CM 4

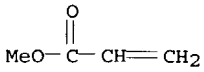
CRN 75-35-4
CMF C2 H2 Cl2



IT **31853-27-7P**, uses and miscellaneous **31853-31-3P**, properties **31853-37-9P**, uses and miscellaneous
RL: SPN (Synthetic preparation); PREP (Preparation)
(preparation of)
RN 31853-27-7 CAPLUS
CN Acrylic acid, polymer with 1,1-dichloroethylene, 2,5-dihydrothiophene 1,1-dioxide and methyl acrylate (8CI) (CA INDEX NAME)

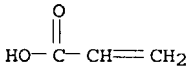
CM 1

CRN 96-33-3
CMF C4 H6 O2



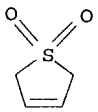
CM 2

CRN 79-10-7
CMF C3 H4 O2



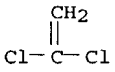
CM 3

CRN 77-79-2
CMF C4 H6 O2 S



CM 4

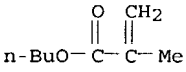
CRN 75-35-4
CMF C2 H2 Cl2



RN 31853-31-3 CAPLUS
CN Methacrylic acid, polymer with butyl methacrylate, 1,1-dichloroethylene and 2,5-dihydrothiophene 1,1-dioxide (8CI) (CA INDEX NAME)

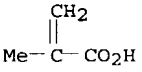
CM 1

CRN 97-88-1
CMF C8 H14 O2



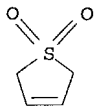
CM 2

CRN 79-41-4
CMF C4 H6 O2



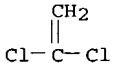
CM 3

CRN 77-79-2
CMF C4 H6 O2 S



CM 4

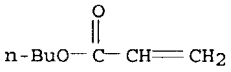
CRN 75-35-4
CMF C2 H2 Cl2



RN 31853-37-9 CAPLUS
CN Acrylic acid butyl ester, polymer with 1,1-dichloroethylene, 2,5-dihydrothiophene 1,1-dioxide and 1-vinyl-2-pyrrolidinone (8CI) (CA INDEX NAME)

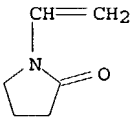
CM 1

CRN 141-32-2
CMF C7 H12 O2



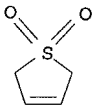
CM 2

CRN 88-12-0
CMF C6 H9 N O



CM 3

CRN 77-79-2
CMF C4 H6 O2 S



CM 4

CRN 75-35-4
CMF C2 H2 Cl2